

10/530349

JC13 Rec'd PCT/PTO 06 APR 2005

Sheet 1 of 1

Form PTO-1449 (REV. 8-83) US Dept. of Commerce PATENT & TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)			ATTY DOCKET NO. 123418	APPLICATION NO. New U.S. National Stage of PCT/JP03/12875		
			APPLICANTS Takahiro KISHIOKA et al.			
			FILING DATE April 6, 2005			
U.S. PATENT DOCUMENTS						
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
<i>NA</i>	1.	2002/0055064 A1	05/09/2002	Etsuko IGUCHI et al.		
<i>CNA</i>	2.	6,284,428 B1	09/04/2001	Takako HIROSAKI et al.		
<i>AFA</i>	3.	6,316,160 B1	11/13/2001	Xie SHAO et al.		
FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)						
EXAMINER <i>R. Ashton</i>					DATE CONSIDERED <i>3/1/07</i>	
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.						

Date: April 6, 2005

5/9/05

Form PTO-1449 (REV. 8-83)		US Dept of Commerce PATENT & TRADEMARK OFFICE	ATTY DOCKET NO. 123418	APPLICATION NO. 10/530,349		
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)		APPLICANTS Takahiro KISHIOKA et al.				
		FILING DATE April 27, 2005				
		U.S. PATENT DOCUMENTS				
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
RA.	1.	5,919,599	07/06/1999	Jim MEADOR et al.		
RA	2.	5,693,691	12/02/1997	Tony D. FLAIM et al.		
RA.	3.	6,323,310 B1	11/27/2001	Rama PULIGADDA et al.		
FOREIGN PATENT DOCUMENTS						
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS
LA.	4.	JP-A-11-511194 w/ trans.	09/28/1999	JAPAN		
	5.	JP-A-10-186671 w/ abst. & trans.	07/14/1998	JAPAN		
	6.	JP-A-2000-187331 w/ abst. & trans.	07/04/2000	JAPAN		
	7.	JP-A-11-279523 w/ abst. & trans.	10/12/1999	JAPAN		
	8.	JP-A-10-204110 w/ abst. & trans.	08/04/1998	JAPAN		
	9.	WO 02/086624 w/ abst.	10/31/2002	WIPO		
	10.	EP I 298 492 A2	04/02/2003	EUROPEAN PATENT OFFICE		
RA.	11.	EP I 298 493 A2	04/02/2003	EUROPEAN PATENT OFFICE		
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)						
RA.	13.	Tom LYNCH et al; "Properties and Performance of Near UV Reflectivity Control Layers"; <i>Advances in Resist Technology and Processing XI</i> , Omkaram Nalamasu ed., <i>Proceedings of SPIE</i> ; Vol. 2195; 1994; pp. 225-229.				
RA.	14.	G. TAYLOR et al.; "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography"; <i>Microlithography 1999: Advances in Resist Technology and Processing XVI</i> , Will Conley ed., <i>Proceedings of SPIE</i> ; Vol. 3678; 1999; pp. 174-185.				
RA.	15.	Jim D. MEADOR et al.; "Recent Progress in 193 nm Antireflective Coatings"; <i>Microlithography 1999: Advances in Resist Technology and Processing XVI</i> , Will Conley ed., <i>Proceedings of SPIE</i> ; Vol. 3678; 1999; pp. 800-809.				
EXAMINER	<i>R. Ashton</i>				DATE CONSIDERED	<i>3/1/07</i>
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3/21/06

Form PTO-1449 (REV. 1/06)		US Dept. of Commerce PATENT & TRADEMARK OFFICE	ATTY DOCKET NO. 123418	APPLICATION NO. 10/530,349
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)		APPLICANTS Takahiro KISHIOKA et al.		
		FILING DATE April 27, 2005		

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Examiner Initials	Cite No.	Document Number	Date	Name
RA	1. ✓	5,250,591	10/05/1993	Ryuichi FUJII et al
	2. ✓	4,874,860	10/17/1989	Bernd GALLENKAMP et al
	3. ✓	6,306,502 B1	10/23/2001	Hiroshi FUKUSHIMA et al
	4. ✓	6,440,568 B1	08/27/2002	Hisayuki KAYANOKI et al
RA	5. ✓	2005/0175927 A1	08/11/2005	Takahiro KISHIOKA et al

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KA	6. ✓	EP 0 098 006	01/11/1984	EUROPE		
	7. ✓	GB 1 286 684	08/23/1972	GREAT BRITAIN		
	8. ✓	JP-A-05-255282	10/05/1993	JAPAN	X	X
	9. ✓	FR 2 629 462	10/06/1989	FRANCE		
	10. ✓	EP 0 869 154 A1	10/07/1998	EUROPE		
	11. ✓	EP 0 922 971 A1	06/16/1999	EUROPE		
KA	12. ✓	EP 1 542 075 A1	06/15/2005	EUROPE		

OTHER DOCUMENTS

Examiner Initials	Cite No.	(Including Author, Title, Date, Pertinent Pages, etc.)
RA	13.	Dirk SCHMALJOHANN et al., "Design Strategies for 157 nm Single-Layer Photoresists: Lithographic Evaluation of a Poly(α -trifluoromethyl vinyl alcohol) Copolymer", <i>Advances in Resist Technology and Processing XVII</i> , Proceedings of SPIE, Vol. 3999 pp 330-334 (2000)
RA	14.	Michael K. CRAWFORD et al., "New materials for 157 nm Photoresists: Characterization and Properties", <i>Advances in Resist Technology and Processing XVII</i> , Proceedings of SPIE, Vol. 3999 pp 357-364 (2000)
KA	15.	Kyle PATTERSON et al., "Polymers for 157 nm Photoresist Applications: A Progress Report", <i>Advances in Resist Technology and Processing XVII</i> , Proceedings of SPIE, Vol. 3999 pp 365-374 (2000)

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R. ASK for

3/1/07